



# 제25회 한국반도체학술대회

The 25<sup>th</sup> Korean Conference on Semiconductors

2018년 2월 5일(월)-7일(수), 강원도 하이원리조트 컨벤션 호텔

2018년 2월 6일(화), 14:10-15:55

Room C (함백, 5층)

## D. Thin Film Process Technology 분과

### [TC2-D] Emerging Thin Film Technology

좌장: 최리노 교수(인하대학교), 이한보람 교수(인천대학교)

TC2-D-1 14:10-14:40	<b>[초청]</b> <b>Atomic Layer Deposition of High-k stacks for DRAM capacitors</b> Ji-Hoon Ahn <sup>1</sup> and Se Hun Kwon <sup>2</sup> <i><sup>1</sup>Department of Electronic Material Engineering, Korea Maritime and Ocean University, <sup>2</sup>School of Materials Science and Engineering, Pusan National University</i>
TC2-D-2 14:40-14:55	<b>Ion Cut-Based Thin Si Layer Transfer on the 8 Inch Full Device Wafer for the Monolithic 3D Integration Scheme</b> Hoonhee Han and Changhwan Choi <i>Division of Materials Science and Engineering, Hanyang University</i>
TC2-D-3 14:55-15:10	<b>Low-Power (~1.5 nJ/spike) Synaptic Events in Cold-Deposited Ti/a-TaO<sub>x</sub>/a-IGZO/Pt Heterostructures on the Flexible PET Substrate</b> Andrey S. Sokolov, Sohyeon Kim, Boncheol Ku, Yawar Abbas, Yu-Rim Jeon, and Changhwan Choi <i>Division of Materials Science and Engineering, Hanyang University</i>
TC2-D-4 15:10-15:25	<b>Efficient Photoelectrochemical Hydrogen Generation Using Molybdenum Disulfide Film on Si Photocathode via Wafer-Scale Atomic Layer Deposition</b> Dae Woong Kim, Dae Hyun Kim, and Tae Joo Park <i>Department of Materials Science and Chemical Engineering, Hanyang University</i>
TC2-D-5 15:25-15:40	<b>Improved Synaptic Behaviors of Ar Plasma-Irradiated ALD HfO<sub>2</sub> ReRAM</b> Boncheol Ku, Sohyeon Kim, Yawar Abbas, Andrey Sergeevich Sokolov, Yu-Rim Jeon, and Changhwan Choi <i>Division of Materials Science and Engineering, Hanyang University</i>
TC2-D-6 15:40-15:55	<b>All-Solution-Processed Flexible Dry-Bioelectrodes for Electrophysiological Sensing</b> Byeong-Cheol Kang and Tae-Jun Ha <i>Department of Electronic Materials Engineering, Kwangwoon University</i>